

11-18-04

IFW



Filed Via Express Mail
Rec. No.: EV 479 701 312 US
On: NOVEMBER 17, 2004

By: 
LINDA E. HASTINGS

Any fee due as a result of this paper, not covered by an
enclosed check, may be charged on Deposit Acct. No. 50-1290.

Attorney Docket No.: NECF 17.638B (100806-00233)

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Inventor: Mami MIYASAKA

Serial No.: 10/657,429

Confirmation No.: 9031

Filed: September 8, 2003

Title: **ELECTRON BEAM EXPOSURE MASK, ELECTRON BEAM
EXPOSURE METHOD, METHOD OF FABRICATING
SEMICONDUCTOR, AND ELECTRON BEAM EXPOSURE
APPARATUS**

Examiner: Anthony G. Quash

Group Art Unit: 2881

Commissioner for Patents
P. O. Box 1450
Alexandria, VA 22313-1450

*Please enter
amendment*

SIR:

Pursuant to 37 C.F.R. §1.312, it is respectfully requested that the following
amendment be entered, this amendment being filed before or on the date of payment of the

Issue Fee: